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Deposition Rates 3 on PVD75 DC/RF Magnetron Sputterer

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Keywords

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Deposition Rates 3 on PVD75 DC/RF Magnetron Sputterer (Graduate Student Fellow Program)

Prepared by Dhruv Turakhia (7/9/2015)

Ni

- Base Pressure: less than 5×10^{-7} Torr
- Process Ar Pressure: 3 mTorr
- DC Power: 400 W
- Deposition Rate: 19.8 ± 0.5 nm/min
- Thickness measurement: P7 stylus profiler

Fe

- Base Pressure: less than 5×10^{-7} Torr
- Process Ar Pressure: 3 mTorr
- DC Power: 400 W
- Deposition Rate: 14.1 ± 0.3 nm/min
- Thickness measurement: P7 stylus profiler